

CS-03-016



March 19, 2004

To: Commissioner for Patents
P.O.Box 1450
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572
28 Davis Avenue
Poughkeepsie, N.Y. 12603

Subject: | Serial No. 10/767,292 01/29/04 |

Hai Cong et al.

A NOVEL METHOD TO CONTROL DUAL
DAMASCENE TRENCH ETCH PROFILE AND
TRENCH DEPTH UNIFORMITY

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation
In An Application.

The following Patents and/or Publications are submitted to
comply with the duty of disclosure under CFR 1.97-1.99 and
37 CFR 1.56.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being
deposited with the United States Postal Service as first class
mail in an envelope addressed to: Commissioner for Patents,
P.O. Box 1450, Alexandria, VA 22313-1450, on March 25, 2004.

Stephen B. Ackerman, Reg.# 37761

Signature/Date Stephen B. Ackerman 3/25/04

CS-03-016

U.S. Patent 6,603,204 to Gates et al., "Low-K Interconnect Structure Comprised of a Multilayer of Spin-on Porous Dielectrics," describes a two layer hard mask structure.

U.S. Patent 6,309,962 to Chen et al., "Film Stack and Etching Sequence for Dual Damascene," teaches that two or three layers of hard mask are not needed in this process using an etch stop layer.

U.S. Patent 6,605,874 to Leu et al., "Method of Making Semiconductor Device Using an Interconnect," discloses a multiple hard mask layer process with no etch stop layer.

U.S. Patent 6,472,306 to Lee et al., "Method of Forming a Dual Damascene Opening Using CVD Low-K Material and Spin-on-Polymer," describes a single hard mask layer and not etch stop layer.

Sincerely,

A handwritten signature in black ink, appearing to read 'S. B. Ackerman', with a stylized flourish at the end.

Stephen B. Ackerman,
Reg. No. 37761

Form PTO-1449

Doc No: (Copies)

License Number

CS-03-016

10 | 767, 292

2025

Hai Cong et al.

Filing Date

01/29/04

Group Art Unit

MAR 29 2004

(1/2) several shots if necessary)

U. S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

[illegible]

OTHER DOCUMENTS (Including Author, Title, Date, Portion, Pages, Etc.)

[illegible]

ΟΙ ΛΙΑΝΕΣ

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.